



**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

in re the Application of

Shinya ARASE et al.

Group Art Unit: 1713

Application No.: 10/078,108

Examiner: H. Pezzuto

Filed: February 20, 2002

Docket No.: 111993

For: BOTTOM ANTI-REFLECTIVE COAT FORMING COMPOSITION FOR  
LITHOGRAPHY

**APPLICANTS' STATEMENT OF SUBSTANCE**  
**OF MARCH 28, 2005, INTERVIEW**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Further to the personal Interview conducted on March 28, Applicants respectfully submit the following remarks, Applicants' separate record of the substance of the interview.

Applicants appreciate the courtesies shown to Applicants' representative by Examiner Pezzuto in the March 28, 2005, telephonic interview.

Claims 4-6 and 8-10 are pending in this application.

During the March 28 personal Interview, the Examiner proposed to amend claim 4 to include 10-95 mol% of component A and 90-5 mol% of component B, and to further include "improved dry etch rates." Applicants' representative agreed to the Examiner's proposed amendment to claim 4. The Examiner agreed that the pending claims appear to be patentable over the cited art, in light of the amendments and arguments presented in the February 4 Amendment.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



James A. Oliff  
Registration No. 27,075

Julie M. Seaman  
Registration No. 51,156

JAO:JMS/jms

Date: May 11, 2005

**OLIFF & BERRIDGE, PLC**  
**P.O. Box 19928**  
**Alexandria, Virginia 22320**  
**Telephone: (703) 836-6400**

<p>DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461</p>
--